PTO/SB/08A (08-00)
Approved for use through 10/31/2002. OMB 0651-0031
U.S. Patent and Trademark Office: U.S. DEPARTMENT OF COMMERCE

U	nder the Par	perwork Re	duction Act	of 1995	, no pers	ons are rec	quired to respond to a collection of	of information unless	it contains	a valid OMB control number.		
	Substitute for form 1449A/PTO						Complete if Known					
	INFO	RMAI	ION I	DISC	CLOS	SURE	Application Number		09/765,388			
STATEMENT BY APPLICANT							Filing Date		January 22, 2001			
	(use as many sheets as necessary)						First Named Inventor		Nobuo SHIMAZU et al.			
1.		(use as m	uny sneets t	us neces.	sary)		Group Art Unit		2881			
<u>ي</u>		·					Examiner Name	Examiner Name		Unknown		
S UE	Sheet	neet 1 of 1					Attorney Docket Number		740107-140			
Š	/						U.S. PATENT DOCUMEN	NTS		30.		
Examiner Initials		Cite No.1	U.S. Patent Document				ne of Patentee or Applicant of Cited	Date of Publication		Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear		
			Number Kind Cod (if known,		xde ²	Document	MM-DD-YY	YY				
_	110		5,831,	272		U'	TSUMI	11-03-1998		-		

					OREIGN PATENT DOC	UMENTS						
Examiner Initials*	Cite No. 1	Office ³	oreign Patent D	Kind Code ³	Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	Le				
		Office	Number ⁴	(if known)								
OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS												
Examiner Initials	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.)., date, page(s), volume-issue number(s), publisher, city and/or country where published.										
DU	/	DISC	LOW ENERGY ELECTRON-BEAM PROXIMITY PROJECTION LITHOGRAPHY: DISCOVERY OF MISSING LINK, TAKAO UTSUMI, J. VAC. SCI. TECHNOL. B 17(6), NOV./DEC. 1999, PP. 2897-2902									
De	/	HIGH THROUGHPUT SUBMICRON LITHOGRAPHY WITH ELECTRON BEAM PROXIMITY PRINTING, H. BOHLEN ET AL., SOLID STATE TECHNOLOGY, SEPTEMBER 1984, PP. 210-217										

^{*}EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Date

Considered

Examiner

Signature

¹ Unique citation designation number. ² See attached Kinds of U.S. Patent Documents. ³ Enter Office that issued the document, by the twoletter code (WIPO Standard ST.3). ⁴ For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵ Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.16 if possible. ⁶ Applicant is to place a check mark here if English language Translation is attached.

¹ Unique citation designation number. ² Applicant is to place a check mark here if English language Translation is attached.